Irradiation damage in semiconductors studied by positron annihilation

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- Introduction: Positrons detect lattice defects
- Examples:
 - electron irradiated Ge
 - neutron-irradiated Si
 - more results
- Conclusions

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The positron lifetime spectroscopy



- positron wave-function can be localized in the attractive potential of a defect
- annihilation parameters
 change in the localized state
- e.g. positron lifetime increases in a vacancy
- lifetime is measured as time difference between 1.27 and 0.51 MeV quanta
- defect identification and quantification possible



Positron lifetime spectroscopy



- positron lifetime spectra consist of exponential decay components
- positron trapping in open-volume defects leads to long-lived components
- longer lifetime due to lower electron density
- analysis by non-linear fitting: lifetimes τ_i and intensities I_i
- positron lifetime spectrum:

$$N(t) = \sum_{i=1}^{k+1} \frac{I_i}{\tau_i} \exp\left(-\frac{t}{\tau_i}\right)$$





Electron-irradiated Ge

- electron irradiation (2 MeV @ 4 K) generates Frenkel pairs
- vacancy annealing and defect reactions may be studied by positrons



(A. Polity and F. Rudolf, Phys. Rev. B **59** (1999) 10025)

- neutron irradiation generates vacancytype defects
- in as-irradiated state at RT:

positron trapping rate: $\kappa = 9.7 \times 10^9 \text{ s}^{-1}$ defect concentration: $C_{def} = 2.5 \times 10^{17} \text{ cm}^{-3}$

- therefore: C_{def} >> [O]
- probably isolated divacancies and larger vacancy clusters

(monovacancies anneal at about 170 K; divacancies stable up to 450...500 K)





• two different vacancy-type defects are detected: divacancies and V₃...V₆





- after annealing of divacancies (673 K annealing step) positron trapping rate: $\kappa = 2 \times 10^9 \text{ s}^{-1}$ assuming $V_4 \implies$ defect concentration: $C_{V4} \approx 2.5 \times 10^{16} \text{ cm}^{-3}$
- annealing stages at 300...600K and at 800 K



Bondarenko et al., unpublished, 2001



- Photoluminescence spectra of similar sample after irradiation show appearance of I2 and I3 lines
- I3 was earlier correlated to small vacancy clusters
- this is in accordance to positron results
- I2 was attributed before to B-B pair defect after B-implantation (impossible explanation here)



H. Feick et al., unpublished, 2001



electron-irradiated GaAs

- electron irradiation generates vacancies in both sublattices
- very complex annealing behavior
- main annealing stage at 300 K
- similar annealing stage found for doped GaAs



A. Polity et al., Phys. Rev. B 55 (1997) 10467



- monovacancy annealing appears around room temperature
- only larger vacancy agglomerates are detectable after neutron irradiation at RT



Polity et al., Appl. Phys. A 60 (1995) 541

Dlubek et al., phys. stat. sol (a) 106 (1988) 81



electron-irradiated InP

- again: complex annealing behavior
- main annealing stage around 200 K
- annealing temperature is function of dose
- around 500 K: vacancy agglomeration



A. Polity and T. Engelbrecht, Phys. Rev. B 55 (1997) 10480



electron-irradiated CuInSe₂

- important solar cell material
- main annealing stage below 150 K
- lowest annealing temperature found in all our experiments
- some defects survive "invisible" up to 550 K
- probably monovacancies in positive charge state (possibly V_{Se})
- divacancies are detected at 600 K with a concentration of about 1×10¹⁷ cm⁻³



A. Polity et al., J. Appl. Phys. 83 (1998) 71



Further techniques of positron annihilation

- VEPAS: Variable-Energy Positron Annihilation Spectroscopy uses monoenergetic positrons of E₊ = 0.1 ... 50 keV for near-surface defect depth profiling; important for thin epitaxial layers or after ion implantation
- Doppler-Coincidence Spectroscopy: annihilations with core electrons give chemical information
- Scanning positron microbeams are available: line-scans and pictures of defect distributions; detailed depth scans by using wedge-shaped samples



Conclusions

- vacancy-type defects can be detected in semiconductors by means of positron annihilation
- lower sensitivity limit for monovacancies $C_v \approx 1 \times 10^{15}$ cm⁻³
- method very sensitive for early stage of vacancy agglomeration
- tools for thin layers (mono-energetic positron beams)
- scanning positron microbeams available

This presentation can be found as pdf-files on our Website: http://www.ep3.uni-halle.de/positrons

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